

MAINTAINING A REACTOR CHAMBER OF
A CHEMICAL VAPOR DEPOSITION SYSTEM

ABSTRACT OF THE DISCLOSURE

Maintaining a reactor chamber of a chemical vapor deposition system includes depositing layers on an inner surface of the reactor chamber, where the layers form an accumulation layer. When the accumulation layer reaches a specified thickness, a plasma clean cycle is performed by introducing cleaning gas into the reactor chamber. The volume of the cleaning gas used during one or more plasma clean cycles is calculated, where the volume indicates the volume of cleaning gas introduced into the reactor chamber. A notification is provided when the volume of the cleaning gas used during the plasma clean cycles has reached a predetermined volume.